

DOUBLE-SIDED EXPOSURE SYSTEM

ABSTRACT

A double-sided exposure system (1) has a first work holding device (21L) for holding a substrate (P) opposite to an exposure mask (55) to expose a first surface of the substrate (P) through the exposure mask (55) to light, and a second work holding device (21R) for holding the substrate (P) opposite to another exposure mask (55) to expose a second surface of the substrate (P) through the exposure mask (55) to light. Phases of operations for receiving, transferring and pretreating an unexposed substrate, and those of operations for transferring, exposing and pretreating the substrate having one surface processed by an exposure operation can be staggered to prevent time loss due to waiting during an exposure operation can be prevented even if the double-sided exposure system is provided with a single light source.

(Fig. 1)